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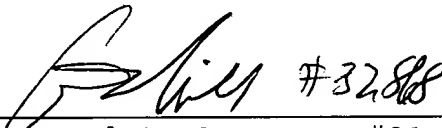
	CLAIMS REMAINING AFTER AMENDMENT		HIGHEST NUMBER PREVIOUSLY PAID FOR		PRESENT EXTRA	RATE	ADDITIONAL FEE
TOTAL	44	-	40	=	4	\$18	\$72.00
INDEPENDENT	10	-	11	=	0	\$84	\$0.00
<input type="checkbox"/> FIRST PRESENTATION OF A MULTIPLE DEPENDENT CLAIM						\$280	\$0.00
						TOTAL	\$72.00

- ☐ Petition for () month(s) extension of time pursuant to 37 C.F.R. §§ 1.17 and 1.136(a). \$0.00 for the extension of time.
- ☐ No fee is required.
- ☒ Check(s) in the amount of \$72.00 is(are) enclosed.
- ☐ Please charge Deposit Account No. 02-2448 in the amount of \$0.00. This form is submitted in triplicate.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. § 1.16 or under 37 C.F.R. § 1.17; particularly, extension of time fees.

Respectfully submitted,

BIRCH, STEWART, KOLASCH & BIRCH, LLP

By  #32888
for Raymond C. Stewart, #21,066

RCS/REG/gml
1248-0472P

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ATTACHMENT

(Rev. 09/27/01)



PATENT
1248-0472P

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IN THE U.S. PATENT AND TRADEMARK OFFICE

APPLICANT: Hideaki FUJITA et al. CONF.: 8686
SERIAL NO: 09/444,460 GROUP: 2874
FILED: November 22, 1999 EXAMINER: S. Knauss
FOR: ORGANIC WAVEGUIDE AND MANUFACTURING METHOD THEREOF
AND OPTICAL PART USING THE SAME

AMENDMENT UNDER 37 C.F.R. § 1.111

Assistant Commissioner for Patents
Washington, D.C. 20231

October 3, 2001

#7, a
Marsha
10/11/01

Sir:

In response to the Examiner's Office Action dated July 3, 2001, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

IN THE SPECIFICATION:

Please replace the paragraph beginning on page 21, line 10, with the following rewritten paragraph:

a --In the silane containing polyimide, the silicon component is not etched in RIE with an oxygen gas and remains, which causes residue. Thus, generation of residue can be suppresses using the polyimide containing no silane.--

Please replace the paragraph beginning on page 24, line 14, with the following rewritten paragraph: